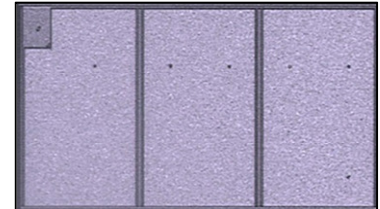


N-Channel Power Trench Mosfet Chip

FDP085N10A

100V, 96A, 8.5mΩ¹

Part	V _{(BR)DSS}	I _{Dn}	R _{DS(on)} Max	Die Size
FDP085N10A	100V	96A	8.5mΩ ¹	2.4 x 4.4 mm ²
See page 2 for ordering part numbers & supply formats				



Applications

- High density AC / DC Converters
- Motor drives & Micro Inverters

Features

- High Power & Current Handling Capability
- Low R_{DS (on)} per mm²
- Low Gate Charge, Fast Switching

Maximum Ratings

Symbol	Parameter	Ratings	Units
V _{DSS}	Drain to Source Voltage	100	V
V _{GSS}	Gate to Source Voltage	±20	V
I _D	Drain Current ²	Continuous (T _C = 25°C)	96
		Continuous (T _C = 100°C)	68
I _{DM}	Drain Current ³	Pulsed	384
T _J , T _{STG}	Operation Junction & Storage Temperature	-55 to 175	°C
E _{AS}	Single Pulsed Avalanche Energy ⁴	L = 3mH, I _{AS} = 13.4A, R _G =25Ω Starting T _J =25°C	269
dv/dt	Peak Diode Recovery dv/dt ⁴	I _{SD} ≤ 96A, di/dt ≤ 200A/μs, V _{DD} ≤ BV _{DSS} Starting T _J =25°C	6

Static Characteristics, T_J = 25° unless otherwise noted

Symbol	Parameter	Test Conditions	Min	Typ	Max	Units
BV _{DSS}	Drain to Source Breakdown Voltage	I _D = 250μA, V _{GS} = 0V	100	-	-	V
V _{GS(th)}	Gate threshold Voltage	V _{GS} = V _{DS} , I _D =250μA	2.0	-	4.0	V
I _{DSS}	Zero Gate Voltage Drain Current	V _{DS} = 80V, V _{GS} = 0V	-	-	1	μA
	Zero Gate Voltage Drain Current @ 150°C	V _{DS} = 80V, V _{GS} = 0V	-	-	500	
I _{GSS}	Gate to Body Leakage Current	V _{GS} = ±20V, V _{DS} = 0V	-	-	±100	nA
R _{DS(on)}	Static Drain to Source On Resistance ¹	V _{GS} = 10V, I _D = 96A	-	7.35	8.5	mΩ

Notes:

1. Defined by chip design, not subject to 100% production test at wafer level
2. Performance will vary based on assembly technique and substrate choice
3. Repetitive Rating: Pulse width limited by maximum junction temperature

Further Information - Contact your [Micross sales office](#) or email your enquiry to baredie@micross.com

Dynamic Characteristics⁴, T_J = 25°C unless otherwise noted

Symbol	Parameter	Test Conditions	Min	Typ	Max	Units
g_{FS}	Forward Transconductance	$V_{DS} = 10V, I_D = 96A$	-	72	-	S
ESR	Equivalent Series Resistance (G-S)	$f = 1MHz$	-	0.97	-	Ω
C_{iss}	Input Capacitance	$V_{DS} = 50V, V_{GS} = 0V$ $f = 1MHz$	-	2025	2695	pF
C_{oss}	Output Capacitance		-	468	620	pF
C_{rss}	Reverse Transfer Capacitance		-	20	-	pF
$C_{oss(er)}$	Energy Related Output Capacitance	$V_{DS} = 50V, V_{GS} = 0V$	-	752	-	pF
$Q_{g(tot)}$	Total Gate Charge at 10V	$V_{DS} = 50V, I_D = 96A$ $V_{GS} = 10V^5$	-	31	40	nC
Q_{gs}	Gate to Source Gate Charge		-	9.7	-	nC
Q_{gs2}	Gate Charge Threshold to Plateau		-	5.0	-	nC
Q_{gd}	Gate to Drain "Miller" Charge		-	7.5	-	nC

Switching Characteristics⁴, T_J = 25°C unless otherwise noted

Symbol	Parameter	Test Conditions	Min	Typ	Max	Units
$t_{d(on)}$	Turn-On Delay Time	$V_{DD} = 50V, I_D = 96A$ $V_{GS} = 10V, R_{GEN} = 4.7\Omega^5$	-	18	46	ns
t_r	Turn-On Rise Time		-	22	54	ns
$t_{d(off)}$	Turn-Off Delay Time		-	29	68	ns
t_f	Turn-Off Fall Time		-	8	26	ns

Drain-Source Diode Characteristics⁴, T_J = 25°C unless otherwise noted

Symbol	Parameter	Test Conditions	Min	Typ	Max	Units
I_S	Maximum Continuous Drain to Source Diode Forward Current		-	-	96	A
I_{SM}	Maximum Pulsed Drain to Source Diode Forward Current		-	-	384	A
V_{SD}	Drain to Source Diode Forward Voltage	$V_{GS} = 0V, I_{SD} = 96A$	-	-	1.3	V
t_{rr}	Reverse Recovery Time	$V_{DD} = 50V, V_{GS} = 0V, I_{SD} = 96A$ $di_F/dt = 100A/\mu s$	-	59	-	ns
Q_{rr}	Reverse Recovery Charge		-	80	-	nC

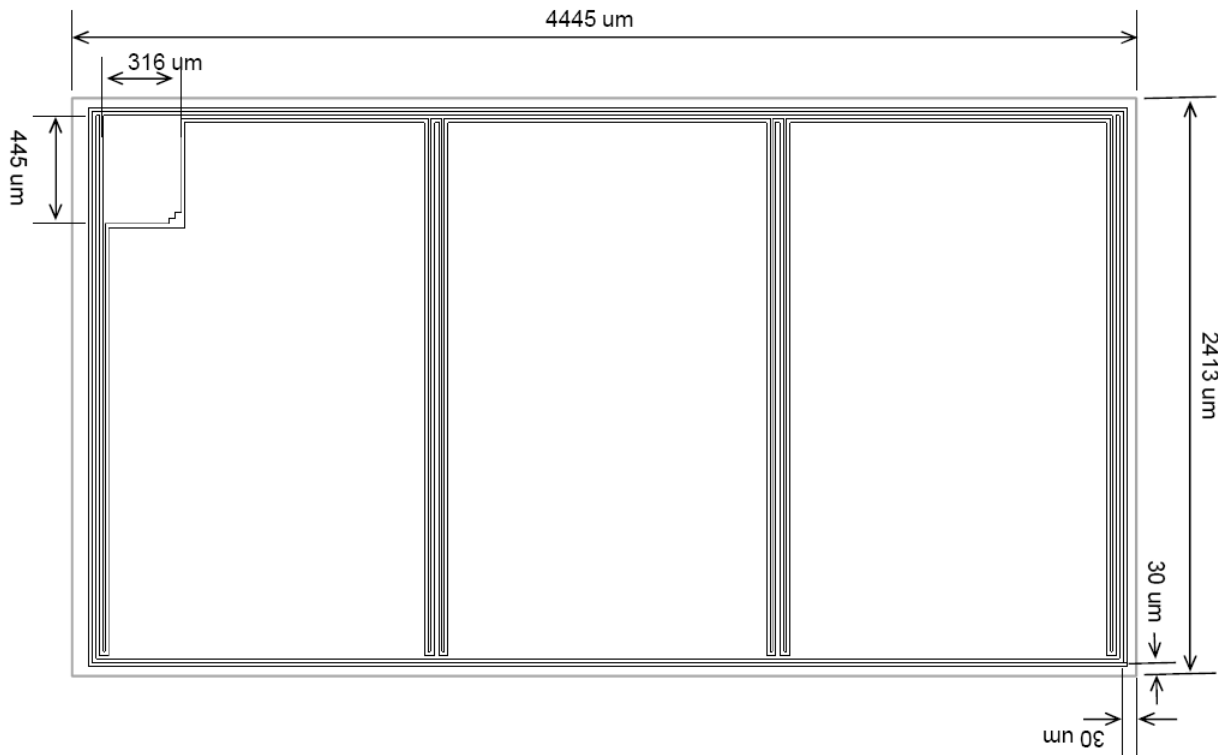
Notes:

- Characterised by design & tested at component level, not subject to production test at wafer level
- Essentially independent of Operating Temperature Typical Characteristics

Ordering Guide

Part Number	Format	Detail / Drawing
FDP085N10AMW	Un-sawn wafer, electrical rejects inked	Page 3
FDP085N10AMWF	Sawn wafer on film-frame	Page 4
FDP085N10AMD	Singulated die / chips in waffle pack	Page 4
Note: Singulated Die / Chips can also be supplied in Pocket Tape or SurfTape® on request		

Die Drawing



Mechanical Data

Parameter			Units
Chip Dimensions Un-sawn	4445 x 2413		μm
Chip Thickness (Nominal)	200		μm
Gate Pad Size	316 x 445		μm
Wafer Diameter	200 (subject to change)		mm
Saw Street	60 (subject to change)		μm
Wafer orientation on frame	Wafer notch parallel with frame flat		
Topside Metallisation & Thickness	Al / Cu +TiW+Ti	4	μm
Backside Metallisation & Thickness	Ti-VNi-Ag	0.65	μm
Topside Passivation	Unpassivated		
Recommended Die Attach Material	Soft Solder or Conductive Epoxy		
Recommended Wire Bond - Gate	Al 125μm X1		
Recommended Wire Bond – Source	Al 500μm X3 double stitch		

